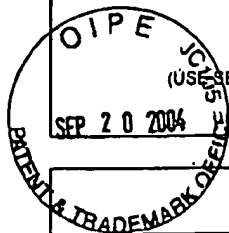


FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.
ASMJP.104DV1APPLICATION NO.
10708,624INFORMATION DISCLOSURE STATEMENT
BY APPLICANT

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APPLICANT
Akira SHIMIZU, et al.FILING DATE
November 12, 2003GROUP
1725

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
M	1.	4,804,431	02/14/89	Aaron RIBNER			
M	2.	4,910,042	03/20/90	Jiri HOKYNAR			
M	3.	5,023,056	06/11/91	Monti E. AKLUF, et al.			
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FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO

EXAMINER
INITIAL

OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)

M	7.	D.F. Weston, et al. HF vapor phase etching (HF/VPE): Production viability for semiconductor manufacturing and reaction model, J. Vac. Scie. Technol., 17(1) Jan./Feb. 1980, 1980 American Vacuum Society, pp. 466-468.

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091604

EXAMINER

M. Asch

DATE CONSIDERED

3-5-03

*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.